

# A 130nm CMOS Evaluation Digitizer Chip for Silicon Strips readout at the ILC



**Thanh Hung PHAM**

on behalf of

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Work in the framework of the SiLC (Silicon for the Linear Collider), R&D Collaboration  
and the EUNET I3-FP6 European Project

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# Outline

- Silicon strips readout
- Front-End Electronics
- A 4-channel evaluation chip in 130nm CMOS
- Conclusion

# Silicon strips detectors at the ILC

Silicon tracker system, two cases considered:  
ILD (Silicon tracking surrounding the TPC and  
SiD (All Silicon tracking)

Both cases end up to:

- A few  $10^6$  Silicon strips
- 10-30 max (could reach 60cm in extreme case) strip length,
- Thickness  $\leq 300 \mu\text{m}$
- Strip pitch  $\leq 50 \mu\text{m}$
- AC coupled (could be DC if needed)

Millions of channels

→ Integration of k-scale channels readout chip

# Silicon strips data

- **Pulse height:** Cluster centroid to get a few  $\mu\text{m}$  position resolution

→ *Detector pulse analog sampling*

- **Time:** 150-300 ns for BC identification

→ *Shaping time of the order of the microsecond depending upon strip length (capacitance)*

→ **80ns analog pulse sampling and on-chip digitization**

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# Functionalities to be integrated

## ● Full readout chain integration in a single chip

- Preamp-shaper
  - Sparsification
  - Sampling
  - Analog event buffering:
  - On-chip digitization
  - Buffering and pre-processing:  
Centroids, least square fits, lossless compression and error codes
  - Calibration and calibration management
  - Power switching (ILC duty cycle)
- Trigger decision on analog sums  
8-deep sampling analog pipe-line  
Occupancy: 8-16 deep event buffer  
10-bit ADC

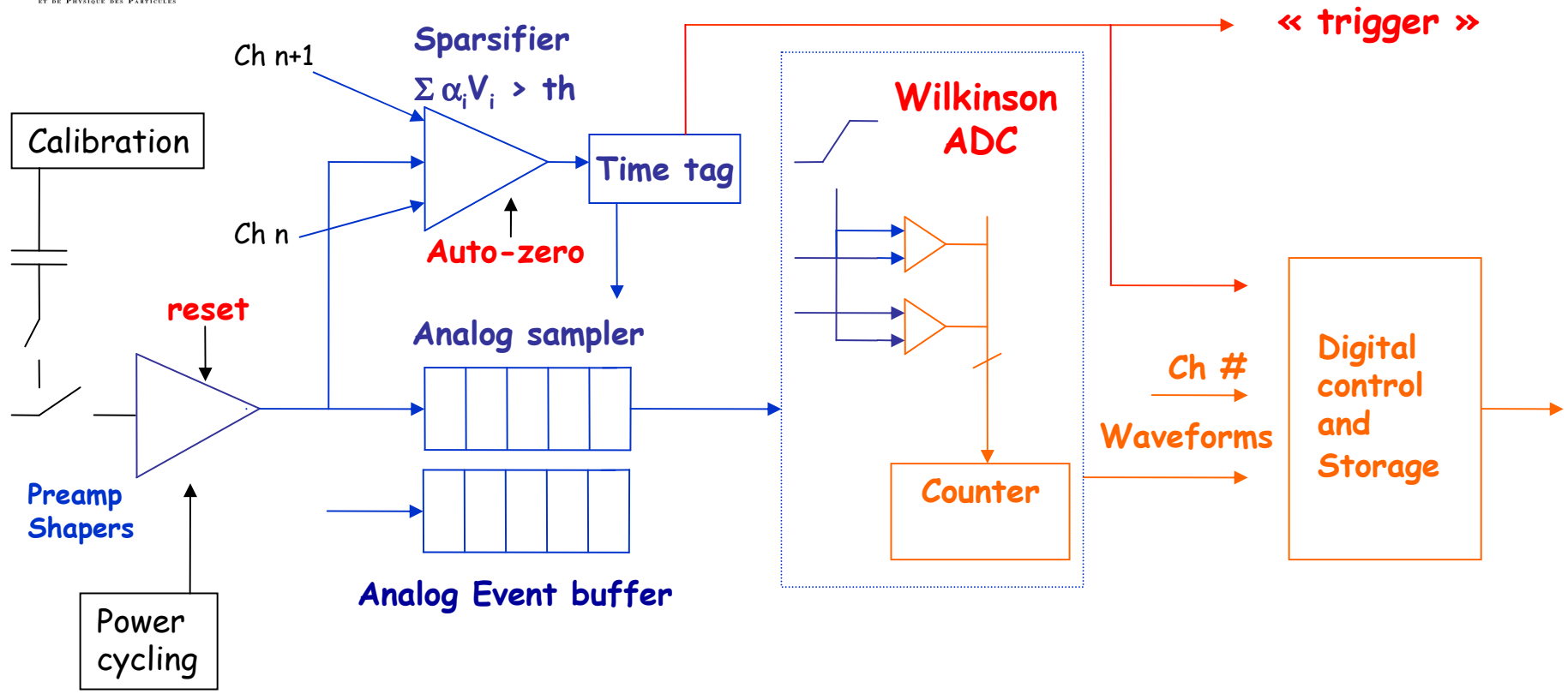
# Front-End chip numbers

- **Goal:** Integrate 512-1024 channels in 90nm CMOS:

- **Amplifiers:** - 30 mV/MIP over 30 MIP range
- **Shapers:** - Two ranges: 500ns–1 $\mu$ s, 1 $\mu$ s-3 $\mu$ s
- **Sparsifier:** - Threshold the sum of 3-5 adjacent channels
- **Samplers:** - 8 samples at 80ns sampling clock period  
- Event buffer 8-16 deep
- **Noise baseline:**  
Measured with 180nm CMOS:  
375 + 10.5 e-/pF @ 3 $\mu$ s shaping, 210 $\mu$ W power  
S/N = 20 @ 90cm long strips
- **ADC:** - 10 bits
- **Buffering, digital pre-processing**
- **Calibration**
- **Power switching can save a factor up to 200**

**ILC timing:** 1 ms: ~ 3000 trains @ 360ns / BC 199ms in between

# Front-end architecture



**Charge 1-30 MIP, Time resolution: BC tagging 150-300ns  
80ns analog pulse sampling**

**Technology: Deep Sub-Micron CMOS 130-90nm**



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# Front-end in 130nm

## *Motivation for 130nm CMOS:*

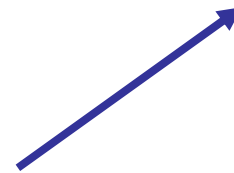
- Smaller
- Faster
- Less power
- Will be (is) dominant in industry
- (More radiation tolerant)

## Drawbacks:

- Reduced voltage swing (Electric field constant)
- Noise slightly increased ( $1/f$ )
- Leaks (gate/subthreshold channel)
- Design rules more constraining
- Models more complex, not always up to date

# UMC CMOS Technology parameters

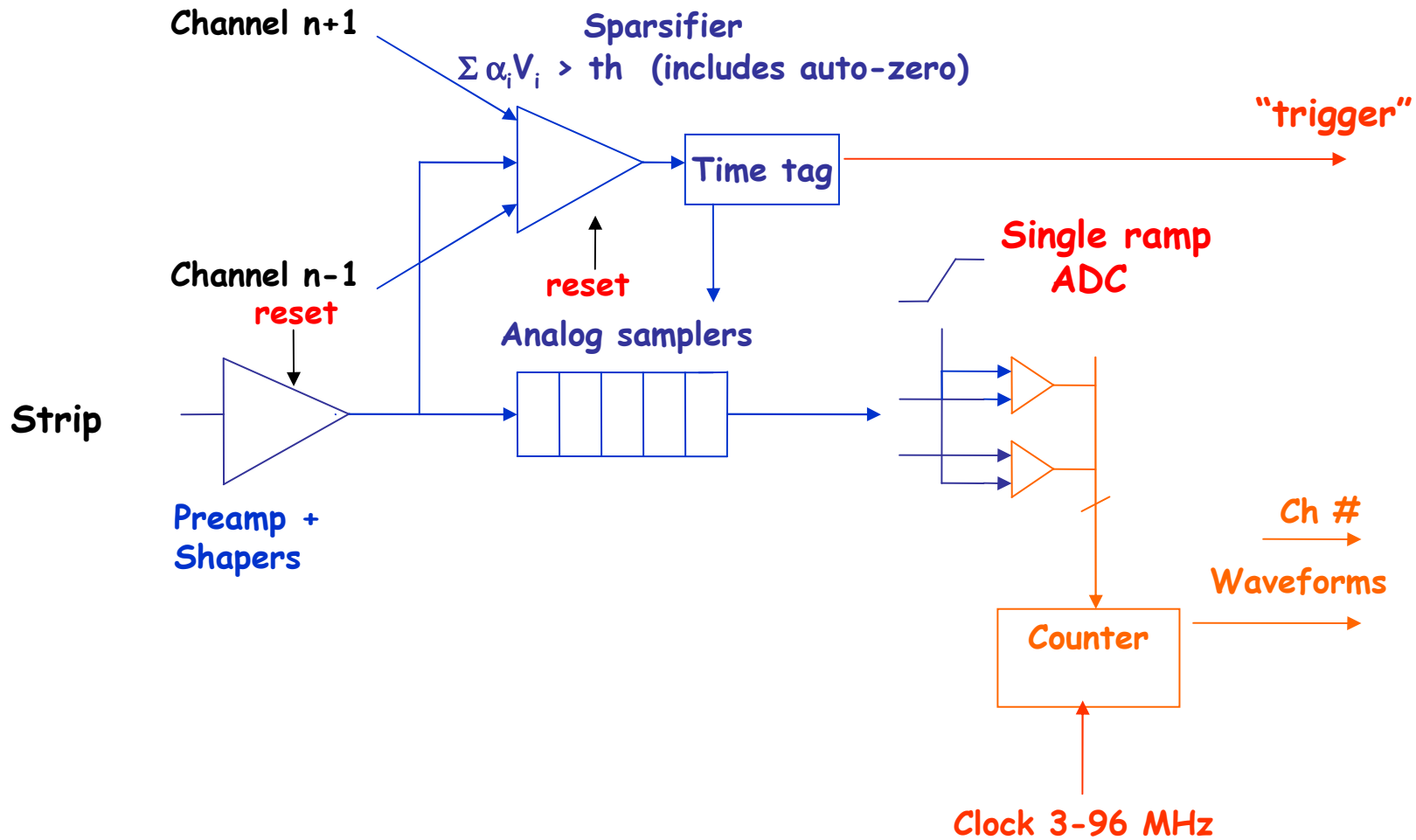
	180 nm	130nm
• 3.3V transistors	yes	yes
• Logic supply	1.8V	1.2V
• Metals layers	6 Al	8 Cu
• MIM capacitors	1fF/ $\mu\text{m}^2$	1.5 fF/ $\mu\text{m}^2$
• Transistors	Three Vt options	Low leakage option



May be used for analog storage during ~ 1 ms

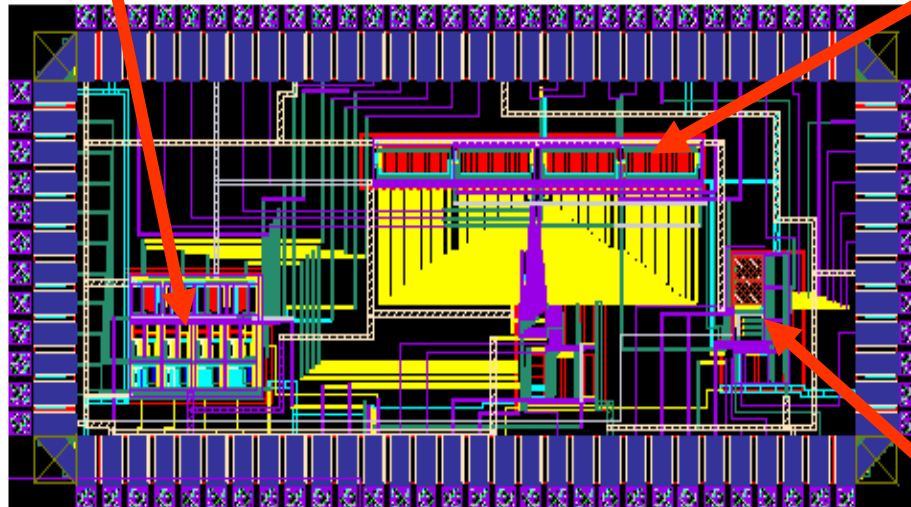
Help from IMEC Europractice (Leuven, Belgium): Paul Malisse, Erwin Deumens

# 4-channel Chip



# 4-channel chip layout

Amplifier, Shaper, Sparsifier  $90 \times 350 \mu\text{m}^2$  Analog sampler  $250 \times 100 \mu\text{m}^2$



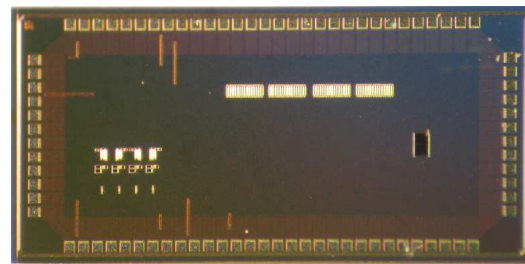
A/D  $90 \times 200 \mu\text{m}^2$



180nm 130nm

Layout of the 130nm chip including sampling and A/D conversion

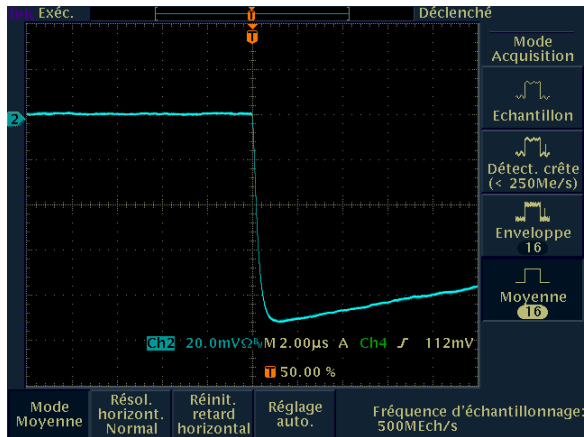
Photo



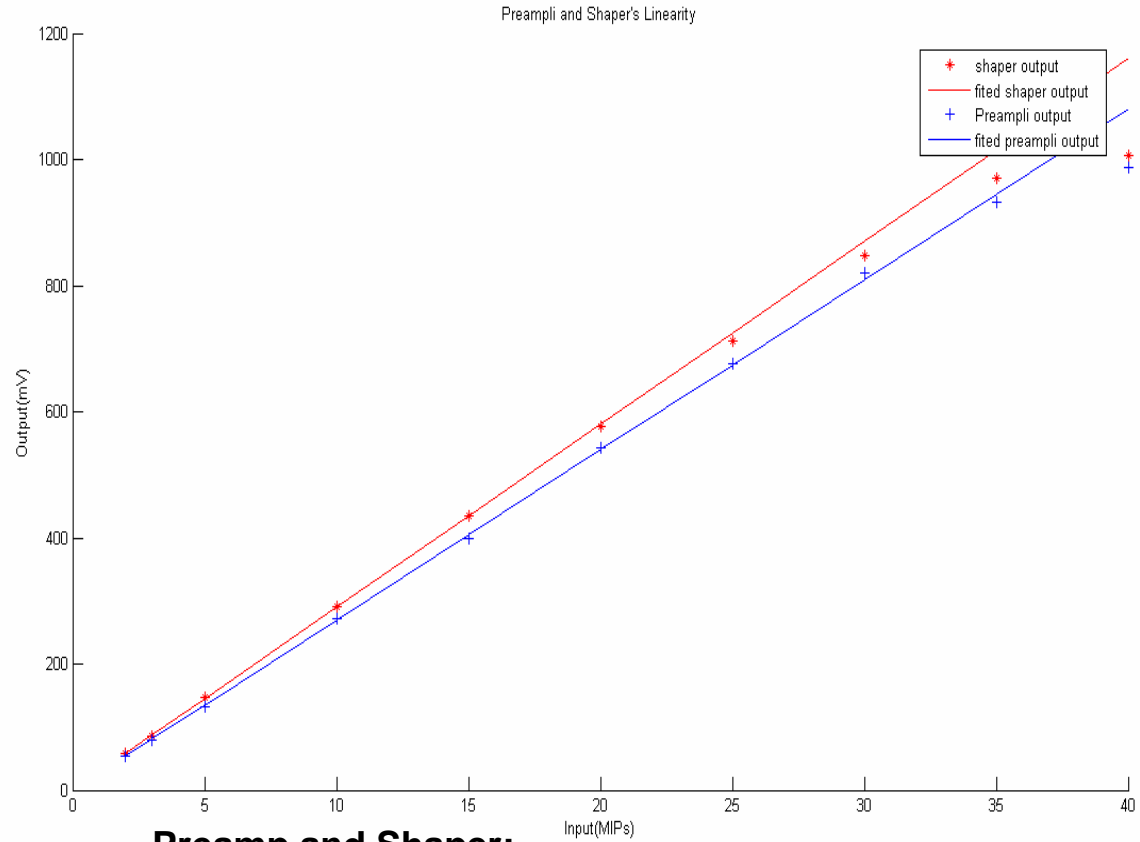
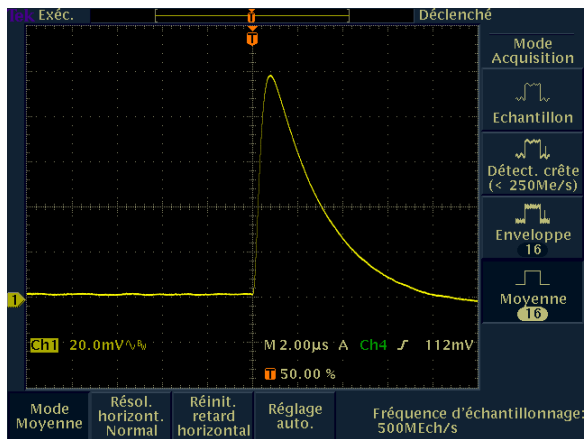
# Preamp-shaper results

## Measured gain - linearities

### Preamp output



### Shaper output

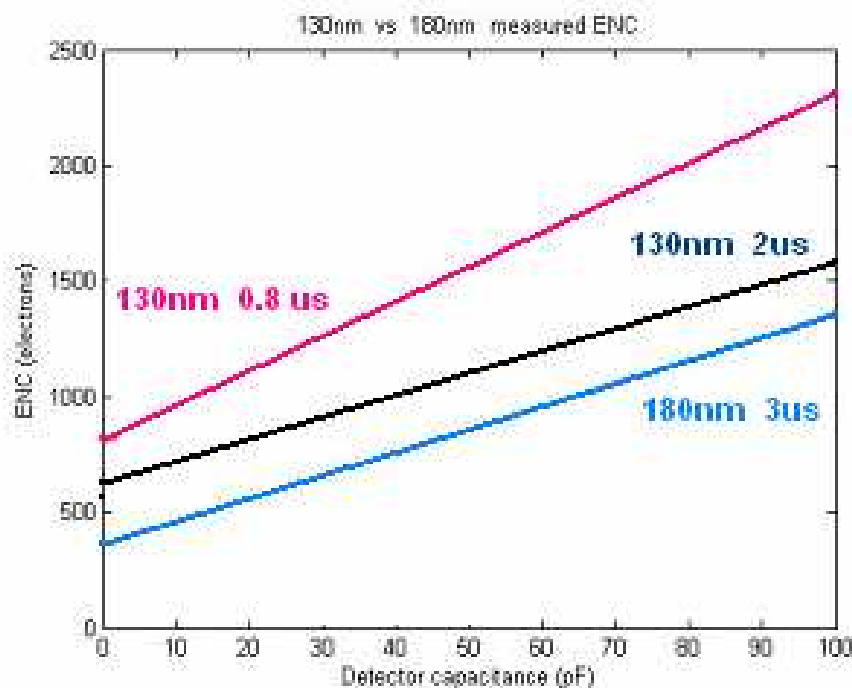


Preamp and Shaper:

Gain = 29mV/MIP  
 Dynamic range = 20 MIPs 1%  
 30 MIPs 5%

Peaking time = 0.8-2.5µs / 0.5-3µs expected

# Noise results



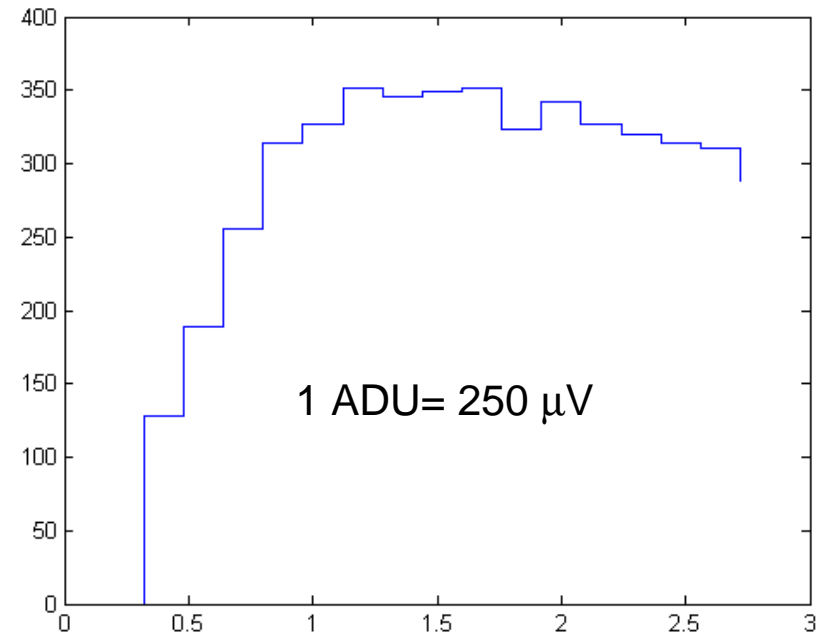
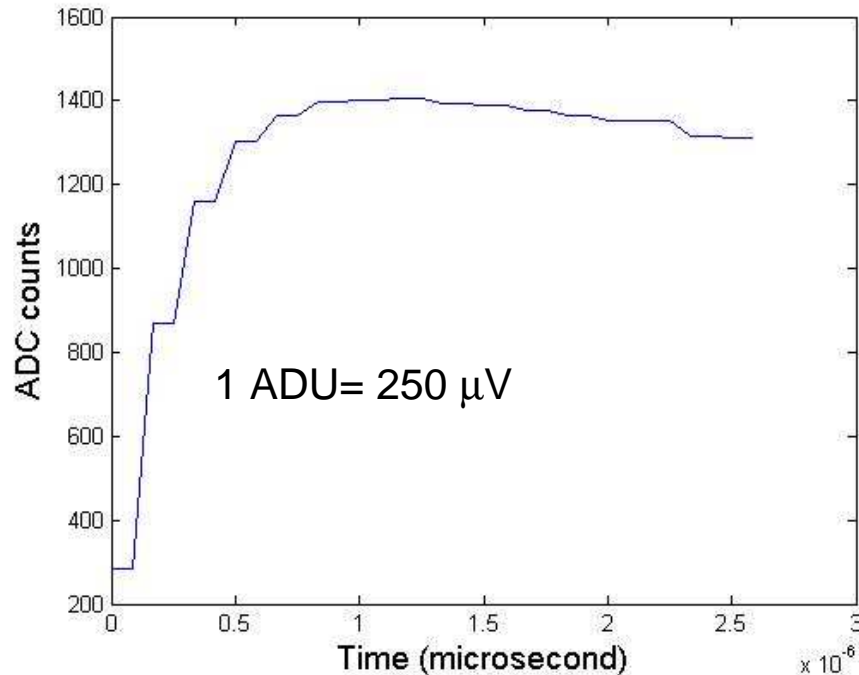
Power (Preamp+ Shaper) = 245  $\mu$ W

Noise:	130nm @ 0.8 $\mu$ s :	850 + 14	e- / pF	245 $\mu$ W	(150+95)
	130nm @ 2 $\mu$ s :	625 + 9	e- / pF		
	180nm @ 3 $\mu$ s :	375 + 10.5	e- / pF	210 $\mu$ W	(70+140)

# Digitized analog pipeline output

## Laser response of detector + 130nm chip

Digitized shaper output



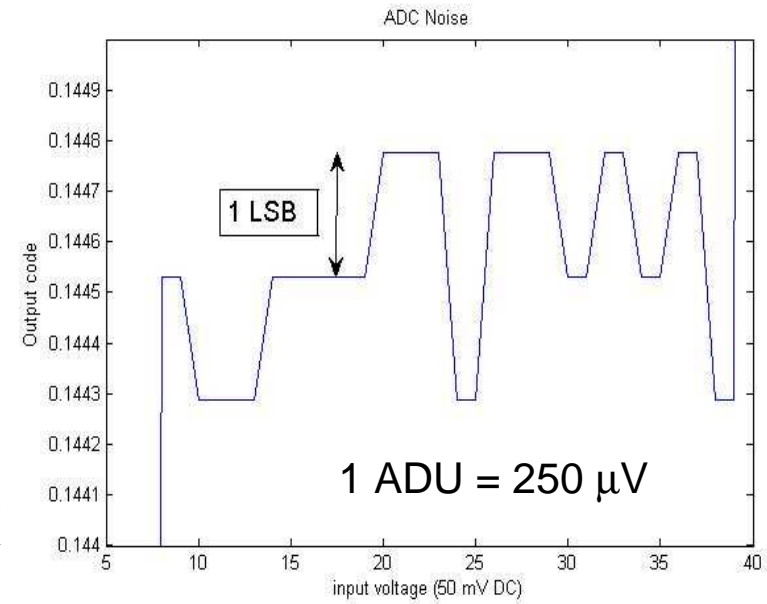
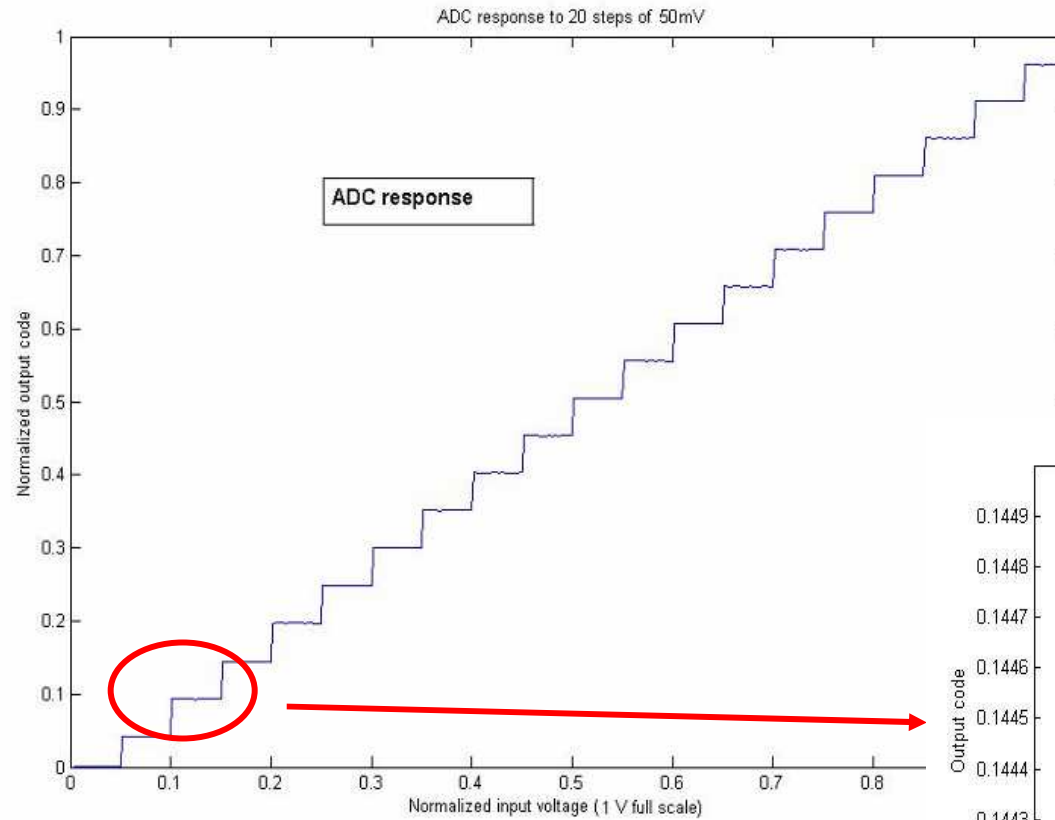
Sampling rate = 12 MHz  
Readout rate = 10 KHz

From calibration pulser as input

From Laser diode + Silicon detector



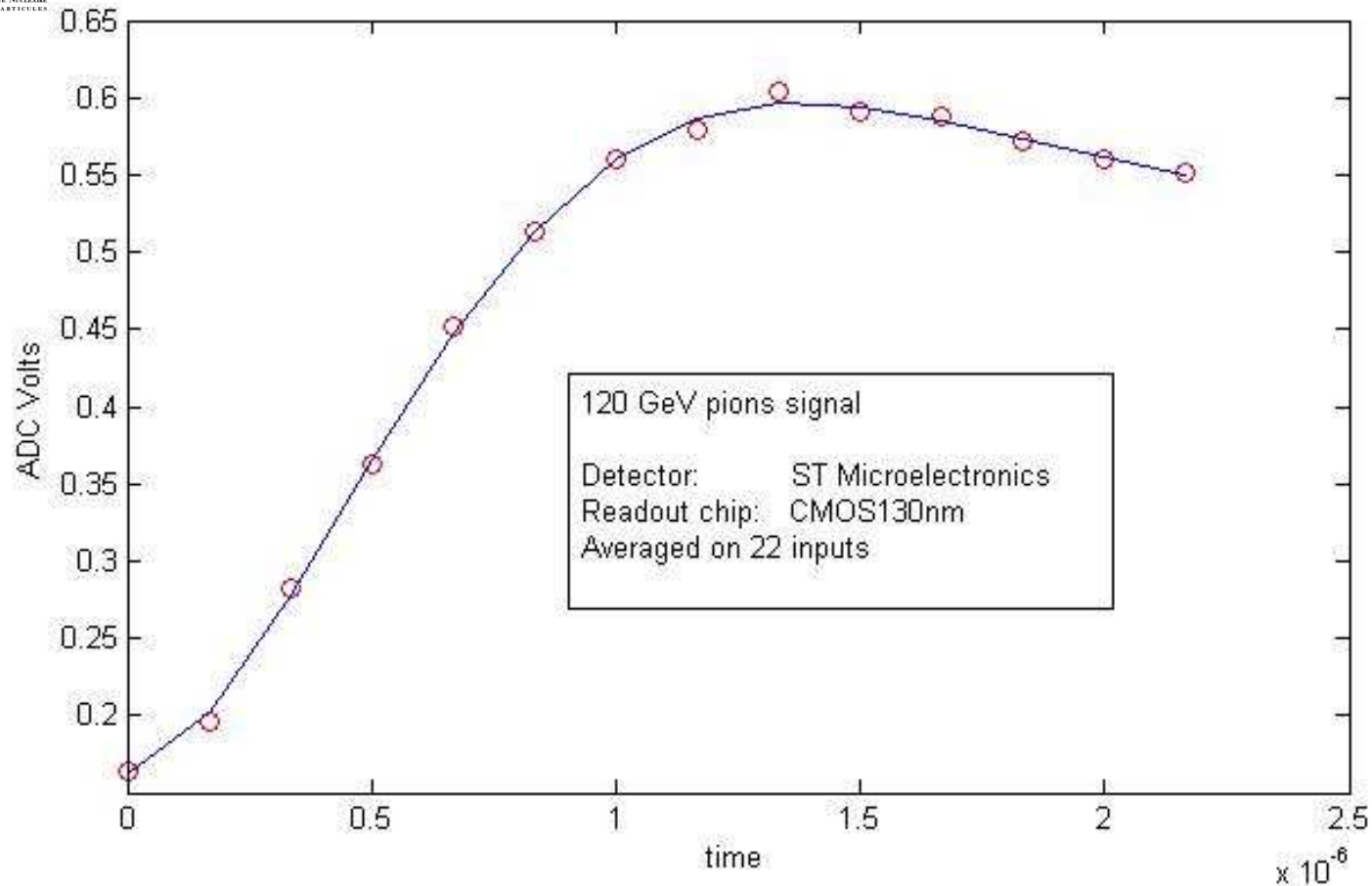
# ADC evaluation



Noise= 4 LSBs

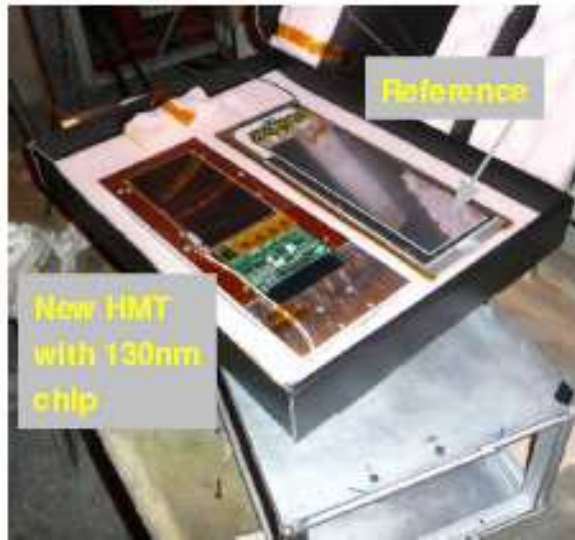
12 bits designed, 10 bits OK

# CERN Beam tests results

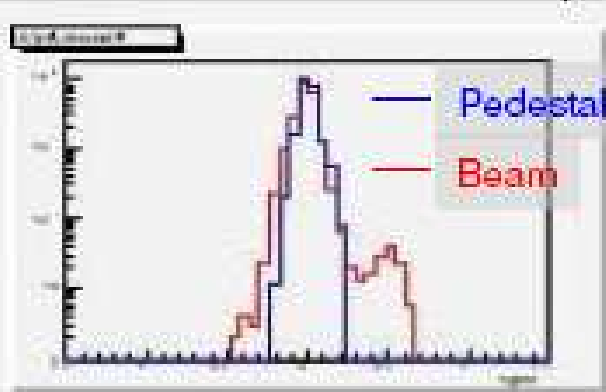


- Averaged response of 120 GeV pions through 500  $\mu\text{m}$  thick Silicon detector
  - Actual pedestal spread: 100mV under investigation (decouplings on PCB)
  - Pedestal subtracted off-line, then digitized shaper waveform OK.
- (see also Jacques David's presentation)

# 130nm chip pedestals/beam response



HMT module with 130 nm chip



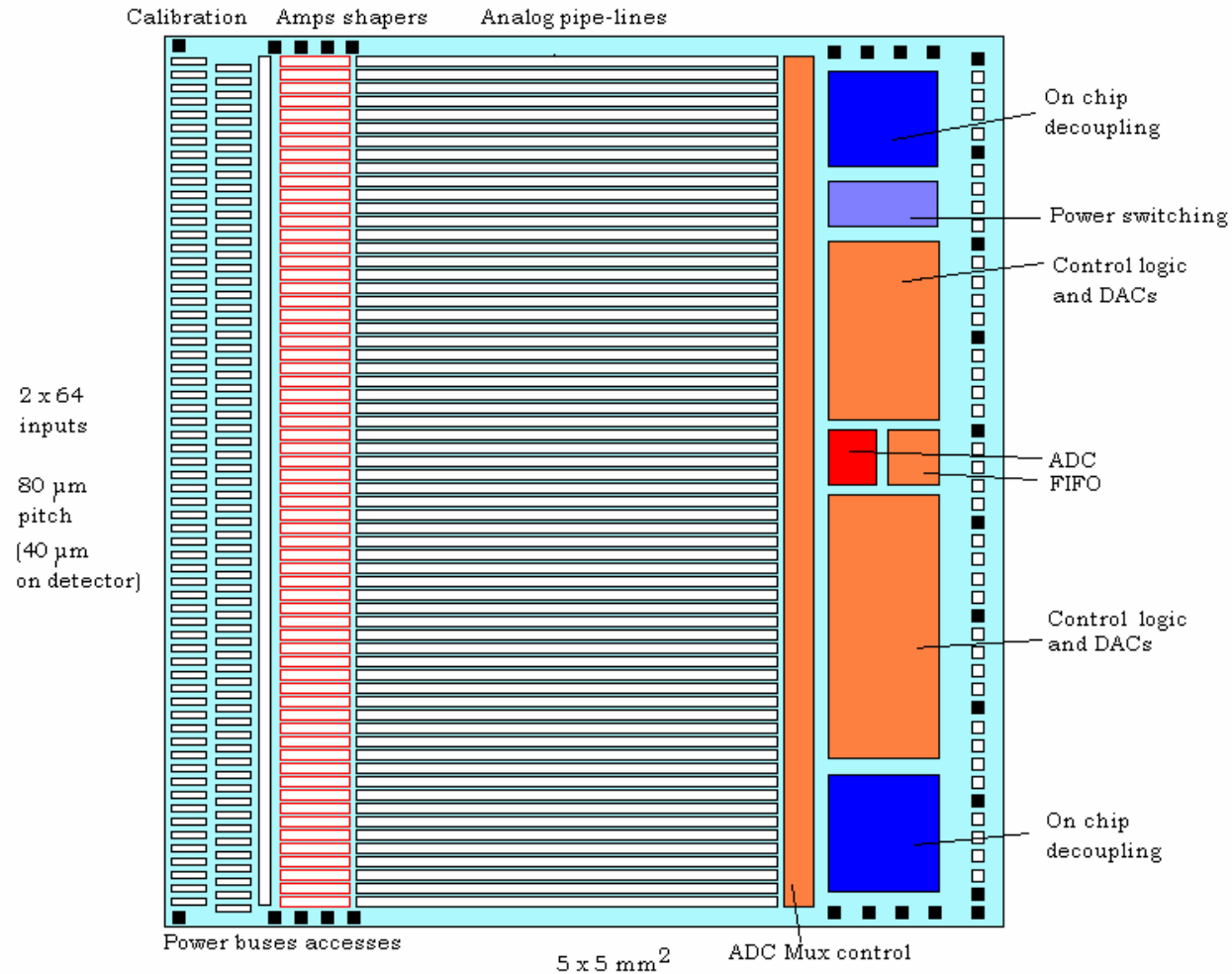
*See also Jacques David's presentation*

# Next chip: Planned Digital

- 128 channels in 130nm CMOS
- Chip control
- Digital buffer
- Processing for :
  - Calibrations
  - Amplitude and time least squares estimation, centroids
  - Raw data lossless compression
- Tools
  - Cadence DSM Place and Route tool
  - Digital libraries in 130nm CMOS available
  - Synthesis from VHDL/Verilog
  - SRAM
  - Some IPs: PLLs

Needs for a mixed-mode simulator

# 128-channel chip



Tentative floor-planning

128 channel chip

UMC CMOS 130nm Mixed-mode process

# Conclusion

*This CMOS 130nm design and first test results demonstrate the feasibility of a highly integrated front-end for Silicon strips (or large pixels) with*

- DC power under  $500\mu\text{W}/\text{ch}$
- Silicon area under  $100 \times 500 \mu^2/\text{ch}$

Allows to design a 128 channel chip starting from validated analog blocks

-> *The 128 channel chip is one main deliverable of the EUDET FP6 EU Project within the JRA2-SiTRA task. It has to equip the forthcoming larger prototypes under construction*

-> *There is a growing effort within the SiLC collaboration for developing this new version and also starting to design the next step in the readout-DAQ system right after the FE chip (see Aurore's talk)*

**The End ...**